IN THE CLAIMS:

The text between "What is claimed is" and Claim No. 1 --CLAIMS FOR CON OF 2269-3846US-- is to be deleted. Claims 5, 20, and 22 have been amended herein. All of the pending claims 1 through 34 are presented, pursuant to 37 C.F.R. §§ 1.121(c)(1)(i) and 1.121(c)(3), in clean form below. Please enter these claims as amended. Also attached is a marked-up version of the claims amended herein pursuant to 37 C.F.R. § 1.121(c)(1)(ii).

CLAIMS

What is claimed is:

- 1. A method for fabricating a chip-scale package, comprising: positioning a preformed polymeric film over a semiconductor device with at least one aperture that extends substantially longitudinally through said preformed polymeric film aligned with a corresponding bond pad of said semiconductor device; and introducing conductive material into said at least one aperture.
- 2. The method of claim 1, further comprising adhering said preformed polymeric film to said semiconductor device.
- 3. The method of claim 1, further comprising defining said at least one aperture through said preformed polymeric film.
 - 4. The method of claim 3, wherein said defining is effected after said positioning.
- 5. (Amended) The method of claim 3, wherein said defining is effected before said positioning.

- 6. The method of claim 1, wherein said introducing comprises bonding said conductive material to said corresponding bond pad.
- 7. The method of claim 1, wherein said introducing comprises depositing said conductive material onto said preformed polymeric film and within said at least one aperture.
- 8. The method of claim 7, wherein said depositing comprises chemical vapor depositing or physical vapor depositing said conductive material.
- 9. The method of claim 1, wherein said introducing comprises placing a preformed conductive structure within said at least one aperture.
 - 10. The method of claim 1, wherein said introducing is effected before said positioning.
 - 11. The method of claim 1, wherein said introducing is effected after said positioning.
- 12. The method of claim 1, further comprising forming at least one contact at an end of said conductive material, opposite said semiconductor device.
- 13. The method of claim 12, further comprising placing a conductive structure adjacent said at least one contact.
- 14. The method of claim 13, wherein said placing comprises applying solder to said at least one contact.
- 15. The method of claim 1, further comprising positioning at least one conductive trace on said preformed polymeric film and in communication with said conductive material.

- 16. The method of claim 15, further comprising forming at least one contact in communication with said conductive trace.
- 17. The method of claim 16, further comprising placing a conductive structure adjacent said at least one contact.
- 18. The method of claim 17, wherein said placing comprises applying solder to said at least one contact.
- 19. The method of claim 1, further comprising placing said preformed polymeric film on at least a portion of a peripheral edge of said semiconductor device.
- 20. (Amended) The method of claim 17, further comprising placing polymeric material at least laterally adjacent said conductive structure.
 - 21. The method of claim 17, further comprising placing a conductive elastomer over at least one conductive structure.
- 22. (Amended) The method of claim 21, further comprising placing another conductive structure in contact with said conductive elastomer, opposite said at least one conductive structure.
 - 23. A method for fabricating a chip-scale package, comprising:

 placing photoimageable polymeric material on a surface of a semiconductor device;

 forming a polymeric film from said photoimageable polymeric material with at least one aperture

 extending substantially longitudinally through said polymeric film, said at least one

 aperture aligned with a corresponding bond pad of said semiconductor device; and

introducing conductive material into said at least one aperture.

- 24. The method of claim 23, wherein said forming comprises selectively exposing regions of said photoimageable polymeric material to electromagnetic radiation.
- 25. The method of claim 23, further comprising defining said at least one aperture through said polymeric film.
 - 26. The method of claim 25, wherein said defining is effected after said forming.
- 27. The method of claim 25, wherein said defining is effected substantially simultaneously with said forming.
- 28. The method of claim 23, further comprising placing at least one conductive trace on said polymeric film and in communication with said conductive material.
- 29. The method of claim 28, further comprising placing at least one contact in communication with said at least one conductive trace.
- 30. The method of claim 29, further comprising placing at least one conductive structure adjacent said at least one contact.
- 31. The method of claim 30, further comprising placing polymeric material at least laterally adjacent said at least one conductive structure.
- 32. The method of claim 30, further comprising placing a conductive elastomer over said at least one conductive structure.

- 33. The method of claim 32, further comprising placing at least one other conductive structure in contact with said conductive elastomer, opposite said at least one conductive structure.
- 34. The method of claim 23, wherein said forming comprises forming said polymeric film so as to extend at least partially over a peripheral edge of said semiconductor device.